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(54) **Negative resist composition, process for forming resist patterns, and process for manufacturing electronic device**

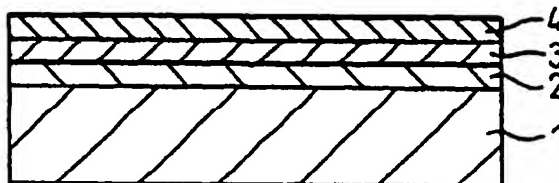
(57) A negative resist composition is provided which comprises at least a constituent component which has a vinyl ether structure protected with an acetal in a molecule thereof. In the formation of negative resist patterns, an aqueous basic solution can be used without swelling.

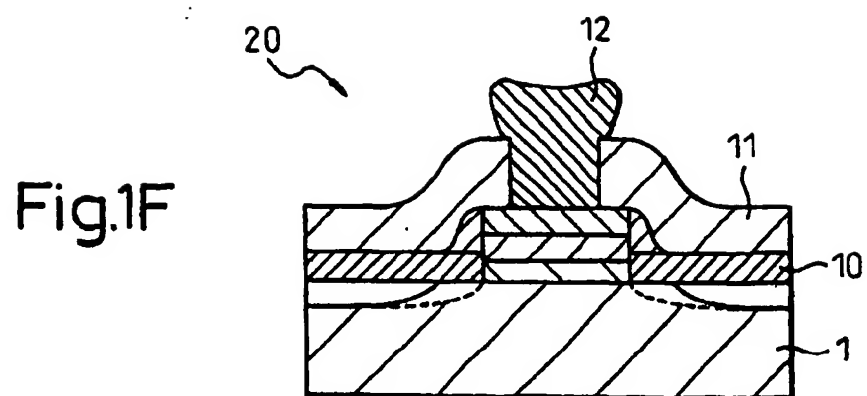
A process is also provided for forming a resist pattern, which comprises the steps of: applying a negative resist composition comprising at least a constituent component which has a vinyl ether structure protected with an acetal in a molecule thereof, on a to-be-treated

substrate; selectively exposing the formed resist film to imaging radiation capable of provoking decomposition of a photo acid generator of the resist composition, and developing the exposed resist film with an aqueous basic solution.

A process is also provided for manufacturing an electronic device, which comprises the step of selectively removing an underlying to-be-treated substrate using a resist pattern, formed from the above-mentioned process, as a masking means to form a predetermined functional element layer.

Fig.1A







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EUROPEAN SEARCH REPORT

Application Number
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Category	Citation of document with indication, where appropriate, of relevant passages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int.Cl.7)
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			TECHNICAL FIELDS SEARCHED (Int.Cl.7)
			G03F
The present search report has been drawn up for all claims			
Place of search THE HAGUE		Date of completion of the search 24 July 2003	Examiner Heywood, C
<p>CATEGORY OF CITED DOCUMENTS</p> <p>X : particularly relevant if taken alone Y : particularly relevant if combined with another document of the same category A : technological background O : non-written disclosure P : intermediate document</p> <p>T : theory or principle underlying the invention E : earlier patent document, but published on, or after the filing date D : document cited in the application L : document cited for other reasons & : member of the same patent family, corresponding document</p>			

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**ANNEX TO THE EUROPEAN SEARCH REPORT
ON EUROPEAN PATENT APPLICATION NO.**

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The members are as contained in the European Patent Office EDP file on
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24-07-2003

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